

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	11226	optic\$3 and semiconductor and substrate and method and etch\$3 and reflection	USPAT	OR	ON	2005/11/18 09:32
S2	12170	optic\$3 and semiconductor and substrate and method and etch\$3 and reflect\$3 and @pd<"20030306"	USPAT	OR	ON	2005/11/07 10:29
S3	2536	S2 and column\$3	USPAT	OR	ON	2005/11/07 10:30
S4	1627	S3 and array	USPAT	OR	ON	2005/11/07 10:35
S5	1110	S4 and ratio	USPAT	OR	ON	2005/11/07 10:30
S6	274	S5 and (silicon adj oxide)	USPAT	OR	ON	2005/11/07 10:31
S7	170	S3 and (lens adj array)	USPAT	OR	ON	2005/11/07 11:25
S8	247	S6 not S7	USPAT	OR	ON	2005/11/07 11:44
S9	417	S8 or S7	USPAT	OR	ON	2005/11/07 11:44
S10	21	(US-6522794-\$ or US-6495813-\$ or US-6475836-\$ or US-RE37809-\$ or US-6197503-\$ or US-6171885-\$ or US-6157429-\$ or US-6124974-\$ or US-6072620-\$ or US-5737300-\$ or US-5654831-\$ or US-5652817-\$ or US-6518640-\$ or US-6516114-\$ or US-6426166-\$ or US-6322936-\$ or US-6177236-\$ or US-5622634-\$ or US-5587335-\$ or US-5449626-\$ or US-4897846-\$).did.	USPAT	OR	OFF	2005/11/07 15:18
S11	0	S10 and chevron	USPAT	OR	OFF	2005/11/07 12:02
S12	30	S2 and chevron	USPAT	OR	OFF	2005/11/07 12:02
S13	447	S9 or S12	USPAT	OR	OFF	2005/11/07 15:19
S14	11	(semiconductor or chip)and trench adj (silicon with oxide)	USPAT	OR	ON	2005/11/07 15:22
S15	47	(semiconductor or chip)and trench near (silicon with oxide)	USPAT	OR	ON	2005/11/07 15:23
S16	0	S15 and optic	USPAT	OR	ON	2005/11/07 15:23
S17	6	S15 and optical	USPAT	OR	ON	2005/11/07 15:23
S18	1	("6733955").PN.	USPAT; USOCR	OR	OFF	2005/11/08 08:03
S19	12	("5399389"   "5665635"   "5786262"   "5851927"   "5930644"   "6030900"   "6287990"   "6372606").PN. OR ("6733955").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/11/08 08:06
S20	0	((micro near lens) near array) and (chip or semiconductor)and (optic or optical) and (trenches near oxidiz\$3)	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/08 08:09

S21	1	((micro near lens) near array) and (chip or semiconductor)and (optic or optical) and (trenches same oxidiz\$3)	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/08 08:14
S22	1	((micro near lens) near array) and (chip or semiconductor)and (optic or optical) and (trenches same anneal\$3)	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/08 08:34
S23	1	((micro near lens) near array) and (chip or semiconductor)and (trenches same anneal\$3)	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/08 08:34
S24	2792	((359/642,641,719,710,619,620) or (216/24)).CCLS.	USPAT; USOCR	OR	OFF	2005/11/15 10:40
S25	584	S24 and etch\$3 and @pd<"20030306"	USPAT	OR	OFF	2005/11/15 14:59
S26	2792	((359/642,641,719,710,619,620) or (216/24)).CCLS.	USPAT; USOCR	OR	OFF	2005/11/15 16:10
S27	584	S26 and etch\$3 and @pd<"20030306"	USPAT	OR	OFF	2005/11/15 14:59
S28	53	S27 and ((anneal\$4 or oxidiz\$3)same substrate)	USPAT	OR	OFF	2005/11/15 15:49
S29	1	S26 and PLZT and Sol-gel	USPAT	OR	OFF	2005/11/15 16:11
S30	0	S26 and ("Blum et al.")	USPAT	OR	OFF	2005/11/15 16:11
S31	41	(US-4897846-\$ or US-5449626-\$ or US-5587335-\$ or US-5622634-\$ or US-5652817-\$ or US-5654831-\$ or US-5737300-\$ or US-6072620-\$ or US-6124974-\$ or US-6157429-\$ or US-6171885-\$ or US-6177236-\$ or US-6197503-\$ or US-6322936-\$ or US-6426166-\$ or US-6472324-\$ or US-6475836-\$ or US-6495813-\$ or US-6516114-\$ or US-6518640-\$ or US-6522794-\$ or US-6733955-\$ or US-RE37809-\$ or US-6517734-\$ or US-6482722-\$ or US-6469832-\$). did. or (US-6403393-\$ or US-6387284-\$ or US-6063299-\$ or US-5925262-\$ or US-5871653-\$ or US-5814237-\$ or US-5632908-\$ or US-5626772-\$ or US-5569355-\$ or US-5500916-\$ or US-5238877-\$ or US-5125946-\$ or US-5431775-\$ or US-5205904-\$ or US-4585299-\$). did.	USPAT	OR	OFF	2005/11/15 16:49
S32	30	S31 and ratio	USPAT	OR	OFF	2005/11/15 16:57
S33	0	S31 and (ratio near oxidiz\$3)	USPAT	OR	OFF	2005/11/15 17:09
S34	18	S31 and matrix	USPAT	OR	OFF	2005/11/15 17:20
S35	1	S31 and (bottom adj wall)	USPAT	OR	OFF	2005/11/16 10:38

S36	2	("0000385").PN.	USPAT; USOCR	OR	OFF	2005/11/16 10:38
S37	1984	(385/?).CCLS.	USPAT; USOCR	OR	OFF	2005/11/16 10:38
S38	4	S37 and ((silicon adj dioxide) same oxidiz\$3)	USPAT	OR	OFF	2005/11/16 10:41
S39	4	S37 and ((silicon adj dioxide) same oxidiz\$4)	USPAT	OR	OFF	2005/11/16 10:41
S40	0	S37 and ((silicon adj dioxide) near oxidiz\$4)	USPAT	OR	OFF	2005/11/16 10:41
S41	210	S37 and (silicon adj dioxide)	USPAT	OR	OFF	2005/11/16 10:41
S42	13	S41 and oxidiz\$3	USPAT	OR	OFF	2005/11/16 10:48
S43	3269	(385/33,37).CCLS.	USPAT; USOCR	OR	OFF	2005/11/16 10:53
S45	1	S43 and (silicon adj dioxide) and trench and oxidiz\$3	USPAT	OR	OFF	2005/11/16 10:50
S46	1	S43 and trench and oxidiz\$3	USPAT	OR	OFF	2005/11/16 10:50
S47	43	S43 and trench	USPAT	OR	OFF	2005/11/16 10:50
S48	5781	(385/33,34,35,36,37,129,130,131,132).CCLS.	USPAT; USOCR	OR	OFF	2005/11/16 10:55
S49	165	S48 and trench	USPAT	OR	OFF	2005/11/16 10:55
S50	13	S49 and oxidiz\$3	USPAT	OR	OFF	2005/11/16 10:55
S51	34	S49 and (oxidiz\$3 or anneal\$3)	USPAT	OR	OFF	2005/11/16 11:13
S52	2	("0000385").PN.	USPAT; USOCR	OR	OFF	2005/11/16 11:13
S53	27594	("385").CLAS.	USPAT; USOCR	OR	OFF	2005/11/16 16:30
S54	534	S53 and trench	USPAT	OR	OFF	2005/11/16 11:13
S55	75	S54 and (anneal\$3 or oxidiz\$4)	USPAT	OR	OFF	2005/11/16 11:26
S56	0	("20030053733").PN.	USPAT; USOCR	OR	OFF	2005/11/16 11:27
S57	0	(2003/0053733).CCLS.	USPAT; USOCR	OR	OFF	2005/11/16 11:29
S58	1	("6748138").PN.	USPAT; USOCR	OR	OFF	2005/11/16 11:29

S59	32	("4474427"   "4725110"   "4740951"   "4807950"   "4852960"   "5029981"   "5042897"   "5048913"   "5061032"   "5104209"   "5216739"   "5367588"   "5388173"   "5495548"   "5500916"   "5652818"   "5726805"   "5822479"   "5898804"   "6023354"   "6031951"   "6035089"   "6084998"   "6101302"   "6169831"   "6459533"   "6490393"   "6522795").PN. OR ("6748138"). URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/11/16 11:29
S60	27594	("385").CLAS.	USPAT; USOCR	OR	OFF	2005/11/17 12:41
S61	0	S60 and "0.55:0.45"	USPAT	OR	OFF	2005/11/16 16:30
S62	27594	("385").CLAS.	USPAT; USOCR	OR	OFF	2005/11/17 12:41
S63	1626	S62 and (contain\$3 near optic\$3)	USPAT	OR	OFF	2005/11/17 12:46
S64	27	S63 and trench	USPAT	OR	OFF	2005/11/17 12:42
S65	189	S62 and (concave adj lens)	USPAT	OR	OFF	2005/11/17 12:47
S66	2	S62 and (concave adj lens)and trench	USPAT	OR	OFF	2005/11/17 12:52
S67	6	S62 and (convex adj lens)and trench	USPAT	OR	OFF	2005/11/17 12:56
S68	0	S62 and (biconvex adj lens)and trench	USPAT	OR	OFF	2005/11/17 12:56
S69	0	S62 and (meniscus adj lens)and trench	USPAT	OR	OFF	2005/11/17 13:25
S70	646	S62 and optic\$4 and trench\$2	USPAT	OR	OFF	2005/11/17 13:26
S71	2792	((359/642,641,719,710,619,620) or (216/24)).CCLS.	USPAT; USOCR	OR	OFF	2005/11/17 13:26
S72	584	S71 and etch\$3 and @pd<"20030306"	USPAT	OR	OFF	2005/11/17 13:26
S73	641	S70 not S72	USPAT	OR	OFF	2005/11/17 13:27
S74	18	S73 and (out\$4 adj trench)	USPAT	OR	OFF	2005/11/17 13:28
S75	44326	("65").CLAS.	USPAT; USOCR	OR	OFF	2005/11/18 09:32
S76	1972	S75 and substrate	USPAT	OR	OFF	2005/11/18 09:33
S77	1805	S76 and @pd <"20040120"	USPAT	OR	OFF	2005/11/18 09:33
S78	4	S77 and trench	USPAT	OR	OFF	2005/11/18 09:38
S79	25715	substrate and trench	USPAT	OR	OFF	2005/11/18 09:38
S80	15996	S79 and @pd<"20030306"	USPAT	OR	OFF	2005/11/18 09:38
S81	14516	S80 and silicon	USPAT	OR	OFF	2005/11/18 09:39
S82	3982	S81 and light	USPAT	OR	OFF	2005/11/18 09:39

S83	1994	S82 and (oxidiz\$3 or anneal\$4)	USPAT	OR	OFF	2005/11/18 09:42
S84	2792	((359/642,641,719,710,619,620) or (216/24)).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 09:42
S85	584	S84 and etch\$3 and @pd<"20030306"	USPAT	OR	OFF	2005/11/18 09:42
S86	53	S85 and ((anneal\$4 or oxidiz\$3)same substrate)	USPAT	OR	OFF	2005/11/18 09:42
S87	1	S84 and PLZT and Sol-gel	USPAT	OR	OFF	2005/11/18 09:42
S88	0	S84 and ("Blum et al.")	USPAT	OR	OFF	2005/11/18 09:42
S89	41	(US-4897846-\$ or US-5449626-\$ or US-5587335-\$ or US-5622634-\$ or US-5652817-\$ or US-5654831-\$ or US-5737300-\$ or US-6072620-\$ or US-6124974-\$ or US-6157429-\$ or US-6171885-\$ or US-6177236-\$ or US-6197503-\$ or US-6322936-\$ or US-6426166-\$ or US-6472324-\$ or US-6475836-\$ or US-6495813-\$ or US-6516114-\$ or US-6518640-\$ or US-6522794-\$ or US-6733955-\$ or US-RE37809-\$ or US-6517734-\$ or US-6482722-\$ or US-6469832-\$). did. or (US-6403393-\$ or US-6387284-\$ or US-6063299-\$ or US-5925262-\$ or US-5871653-\$ or US-5814237-\$ or US-5632908-\$ or US-5626772-\$ or US-5569355-\$ or US-5500916-\$ or US-5238877-\$ or US-5125946-\$ or US-5431775-\$ or US-5205904-\$ or US-4585299-\$). did.	USPAT	OR	OFF	2005/11/18 09:42
S90	1984	(385/?).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 09:42
S91	4	S90 and ((silicon adj dioxide) same oxidiz\$3)	USPAT	OR	OFF	2005/11/18 09:42
S92	210	S90 and (silicon adj dioxide)	USPAT	OR	OFF	2005/11/18 09:42
S93	13	S92 and oxidiz\$3	USPAT	OR	OFF	2005/11/18 09:42
S94	3269	(385/33,37).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 09:42
S95	43	S94 and trench	USPAT	OR	OFF	2005/11/18 09:42
S96	5781	(385/33,34,35,36,37,129,130,131, 132).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 09:42
S97	165	S96 and trench	USPAT	OR	OFF	2005/11/18 09:42
S98	34	S97 and (oxidiz\$3 or anneal\$3)	USPAT	OR	OFF	2005/11/18 09:42
S99	27594	("385").CLAS.	USPAT; USOCR	OR	OFF	2005/11/18 09:42
S100	2	S99 and (concave adj lens)and trench	USPAT	OR	OFF	2005/11/18 09:42

S10 1	646	S99 and optic\$4 and trench\$2	USPAT	OR	OFF	2005/11/18 09:42
S10 2	2792	((359/642,641,719,710,619,620) or (216/24)).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 09:42
S10 3	584	S102 and etch\$3 and @pd<"20030306"	USPAT	OR	OFF	2005/11/18 09:42
S10 4	641	S101 not S103	USPAT	OR	OFF	2005/11/18 09:42
S10 5	18	S104 and (out\$4 adj trench)	USPAT	OR	OFF	2005/11/18 09:42
S10 6	707	S105 or S100 or S91 or S93 or S95 or S98 or S86 or S87 or S85 or S89 or S88	USPAT	OR	OFF	2005/11/18 09:43
S10 7	1977	S83 not S106	USPAT	OR	OFF	2005/11/18 09:44
S10 8	1975	S107 and (process or method)	USPAT	OR	ON	2005/11/18 09:45
S10 9	643	S108 and (optical or optics)	USPAT	OR	ON	2005/11/18 09:45
S11 0	526	S109 and etch	USPAT	OR	ON	2005/11/18 15:02
S11 1	25715	substrate and trench	USPAT	OR	OFF	2005/11/18 15:03
S11 2	15996	S111 and @pd<"20030306"	USPAT	OR	OFF	2005/11/18 15:03
S11 3	14516	S112 and silicon	USPAT	OR	OFF	2005/11/18 15:03
S11 4	3982	S113 and light	USPAT	OR	OFF	2005/11/18 15:03
S11 5	1994	S114 and (oxidiz\$3 or anneal\$4)	USPAT	OR	OFF	2005/11/18 15:03
S11 6	2792	((359/642,641,719,710,619,620) or (216/24)).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 15:03
S11 7	584	S116 and etch\$3 and @pd<"20030306"	USPAT	OR	OFF	2005/11/18 15:03
S11 8	53	S117 and ((anneal\$4 or oxidiz\$3)same substrate)	USPAT	OR	OFF	2005/11/18 15:03
S11 9	1	S116 and PLZT and Sol-gel	USPAT	OR	OFF	2005/11/18 15:03
S12 0	0	S116 and ("Blum et al.")	USPAT	OR	OFF	2005/11/18 15:03

S12 1	41	(US-4897846-\$ or US-5449626-\$ or US-5587335-\$ or US-5622634-\$ or US-5652817-\$ or US-5654831-\$ or US-5737300-\$ or US-6072620-\$ or US-6124974-\$ or US-6157429-\$ or US-6171885-\$ or US-6177236-\$ or US-6197503-\$ or US-6322936-\$ or US-6426166-\$ or US-6472324-\$ or US-6475836-\$ or US-6495813-\$ or US-6516114-\$ or US-6518640-\$ or US-6522794-\$ or US-6733955-\$ or US-RE37809-\$ or US-6517734-\$ or US-6482722-\$ or US-6469832-\$), did. or (US-6403393-\$ or US-6387284-\$ or US-6063299-\$ or US-5925262-\$ or US-5871653-\$ or US-5814237-\$ or US-5632908-\$ or US-5626772-\$ or US-5569355-\$ or US-5500916-\$ or US-5238877-\$ or US-5125946-\$ or US-5431775-\$ or US-5205904-\$ or US-4585299-\$), did.	USPAT	OR	OFF	2005/11/18 15:03
S12 2	1984	(385/?).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 15:03
S12 3	4	S122 and ((silicon adj dioxide) same oxidiz\$3)	USPAT	OR	OFF	2005/11/18 15:03
S12 4	210	S122 and (silicon adj dioxide)	USPAT	OR	OFF	2005/11/18 15:03
S12 5	13	S124 and oxidiz\$3	USPAT	OR	OFF	2005/11/18 15:03
S12 6	3269	(385/33,37).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 15:03
S12 7	43	S126 and trench	USPAT	OR	OFF	2005/11/18 15:03
S12 8	5781	(385/33,34,35,36,37,129,130,131,132).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 15:03
S12 9	165	S128 and trench	USPAT	OR	OFF	2005/11/18 15:03
S13 0	34	S129 and (oxidiz\$3 or anneal\$3)	USPAT	OR	OFF	2005/11/18 15:03
S13 1	27594	("385").CLAS.	USPAT; USOCR	OR	OFF	2005/11/18 15:03
S13 2	2	S131 and (concave adj lens)and trench	USPAT	OR	OFF	2005/11/18 15:03
S13 3	646	S131 and optic\$4 and trench\$2	USPAT	OR	OFF	2005/11/18 15:03
S13 4	2792	((359/642,641,719,710,619,620) or (216/24)).CCLS.	USPAT; USOCR	OR	OFF	2005/11/18 15:03
S13 5	584	S134 and etch\$3 and @pd<"20030306"	USPAT	OR	OFF	2005/11/18 15:03

S13 6	641	S133 not S135	USPAT	OR	OFF	2005/11/18 15:03
S13 7	18	S136 and (out\$4 adj trench)	USPAT	OR	OFF	2005/11/18 15:03
S13 8	707	S137 or S132 or S123 or S125 or S127 or S130 or S118 or S119 or S117 or S121 or S120	USPAT	OR	OFF	2005/11/18 15:03
S13 9	1977	S115 not S138	USPAT	OR	OFF	2005/11/18 15:03
S14 0	1975	S139 and (process or method)	USPAT	OR	ON	2005/11/18 15:03
S14 1	643	S140 and (optical or optics)	USPAT	OR	ON	2005/11/18 15:03
S14 2	526	S141 and etch	USPAT	OR	ON	2005/11/18 15:03
S14 3	279	S142 and (isolat\$3 same trench)	USPAT	OR	ON	2005/11/18 15:04
S14 4	204	S143 and (isolat\$3 near trench)	USPAT	OR	ON	2005/11/18 15:08
S14 5	248	(process or method) and (cut\$4 near substrate) and optic\$4 and convex	USPAT	OR	ON	2005/11/21 10:37
S14 6	1	("5628917").PN.	USPAT; USOCR	OR	OFF	2005/11/21 10:45
S14 7	1	S146 and ratio	USPAT	OR	OFF	2005/11/21 10:45